

Mikko Ritala

List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

526
papers

23,469
citations

74
h-index

126
g-index

565
ext. papers

25,100
ext. citations

4.7
avg, IF

6.92
L-index

#	Paper	IF	Citations
526	Ambient pressure x-ray photoelectron spectroscopy setup for synchrotron-based in situ and operando atomic layer deposition research.. <i>Review of Scientific Instruments</i> , 2022 , 93, 013905	1.7	2
525	Atomic layer deposition of GdF ₃ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2022 , 40, 022402	2.9	0
524	Inter-laboratory workflow for forensic applications: Classification of car glass fragments.. <i>Forensic Science International</i> , 2022 , 333, 111216	2.6	1
523	Reaction mechanism studies on atomic layer deposition process of AlF ₃ . <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2022 , 40, 022401	2.9	0
522	Osteoblast Attachment on Titanium Coated with Hydroxyapatite by Atomic Layer Deposition. <i>Biomolecules</i> , 2022 , 12, 654	5.9	1
521	Combining Experimental and DFT Investigation of the Mechanism Involved in Thermal Etching of Titanium Nitride Using Alternate Exposures of NbF ₅ and CCl ₄ , or CCl ₄ Only. <i>Advanced Materials Interfaces</i> , 2021 , 8, 2101085	4.6	2
520	Observed and Modeled Black Carbon Deposition and Sources in the Western Russian Arctic 1800-2014. <i>Environmental Science & Technology</i> , 2021 , 55, 4368-4377	10.3	1
519	Atomic layer deposition of TbF ₃ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021 , 39, 022404	2.9	2
518	Atomic Layer Deposition of Insulating AlF ₃ /Polyimide Nanolaminate Films. <i>Coatings</i> , 2021 , 11, 355	2.9	1
517	Synchronizing gas injections and time-resolved data acquisition for perturbation-enhanced APXPS experiments. <i>Review of Scientific Instruments</i> , 2021 , 92, 044101	1.7	2
516	Thermal Atomic Layer Etching of Aluminum Oxide (Al ₂ O ₃) Using Sequential Exposures of Niobium Pentafluoride (NbF ₅) and Carbon Tetrachloride (CCl ₄): A Combined Experimental and Density Functional Theory Study of the Etch Mechanism. <i>Chemistry of Materials</i> , 2021 , 33, 2883-2893	9.6	6
515	Highly Material Selective and Self-Aligned Photo-assisted Atomic Layer Deposition of Copper on Oxide Materials. <i>Advanced Materials Interfaces</i> , 2021 , 8, 2100014	4.6	3
514	Oxidative MLD of Conductive PEDOT Thin Films with EDOT and ReCl as Precursors. <i>ACS Omega</i> , 2021 , 6, 17545-17554	3.9	6
513	In Situ Positron Annihilation Spectroscopy Analysis on Low-Temperature Irradiated Semiconductors, Challenges and Possibilities. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2021 , 218, 2000232	1.6	2
512	Sb-doped zirconium dioxide submicron fibers for separation of pertechnetate (TcO ₄ ⁻) from aqueous solutions. <i>Separation Science and Technology</i> , 2021 , 56, 2338-2350	2.5	2
511	Thermal gas-phase etching of titanium nitride (TiN) by thionyl chloride (SOCl ₂). <i>Applied Surface Science</i> , 2021 , 540, 148309	6.7	2
510	Effect of polyethylene wax/soy protein-based dispersion barrier coating on the physical, mechanical, and barrier characteristics of paperboards 2021 , 18, 247-257		2

509	Role of ALD AlO Surface Passivation on the Performance of p-Type CuO Thin Film Transistors. <i>ACS Applied Materials & Interfaces</i> , 2021 , 13, 4156-4164	9.5	15
508	Novel electroblowing synthesis of tin dioxide and composite tin dioxide/silicon dioxide submicron fibers for cobalt(ii) uptake.. <i>RSC Advances</i> , 2021 , 11, 15245-15257	3.7	0
507	Highly conductive and stable CoS thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. <i>Dalton Transactions</i> , 2021 , 50, 13264-13275	4.3	
506	Understanding the Stabilizing Effects of Nanoscale Metal Oxide and Li-Metal Oxide Coatings on Lithium-Ion Battery Positive Electrode Materials. <i>ACS Applied Materials & Interfaces</i> , 2021 , 13, 42773-42796	9.5	6
505	Self-Aligned Thin-Film Patterning by Area-Selective Etching of Polymers. <i>Coatings</i> , 2021 , 11, 1124	2.9	1
504	Atomic Layer Deposition of 2D Metal Dichalcogenides for Electronics, Catalysis, Energy Storage, and Beyond. <i>Advanced Materials Interfaces</i> , 2021 , 8, 2001677	4.6	12
503	Magnetic properties and resistive switching in mixture films and nanolaminates consisting of iron and silicon oxides grown by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020 , 38, 042405	2.9	2
502	Area-Selective Molecular Layer Deposition of Polyimide on Cu through Cu-Catalyzed Formation of a Crystalline Interchain Polyimide. <i>Chemistry of Materials</i> , 2020 , 32, 5073-5083	9.6	8
501	Effect of interstitial carbon on the evolution of early-stage irradiation damage in equi-atomic FeMnNiCoCr high-entropy alloys. <i>Journal of Applied Physics</i> , 2020 , 127, 025103	2.5	13
500	Silicon oxide-niobium oxide mixture films and nanolaminates grown by atomic layer deposition from niobium pentaethoxide and hexakis(ethylamino) disilane. <i>Nanotechnology</i> , 2020 , 31, 195713	3.4	3
499	High-temperature X-ray scattering studies of atomic layer deposited IrO ₂ . <i>Journal of Applied Crystallography</i> , 2020 , 53, 369-380	3.8	1
498	Photocatalytic and Gas Sensitive Multiwalled Carbon Nanotube/TiO-ZnO and ZnO-TiO Composites Prepared by Atomic Layer Deposition. <i>Nanomaterials</i> , 2020 , 10,	5.4	9
497	Van der Waals epitaxy of continuous thin films of 2D materials using atomic layer deposition in low temperature and low vacuum conditions. <i>2D Materials</i> , 2020 , 7, 011003	5.9	13
496	Ionic conductivity in Li _x TaO _y thin films grown by atomic layer deposition. <i>Electrochimica Acta</i> , 2020 , 361, 137019	6.7	3
495	Controlling Atomic Layer Deposition of 2D Semiconductor SnS ₂ by the Choice of Substrate. <i>Advanced Materials Interfaces</i> , 2020 , 7, 2001046	4.6	4
494	Atomic Layer Deposition of PbS Thin Films at Low Temperatures. <i>Chemistry of Materials</i> , 2020 , 32, 8216-8228	8.2	7
493	In Situ Reaction Mechanism Study on Atomic Layer Deposition of Intermetallic Co ₃ Sn ₂ Thin Films. <i>Chemistry of Materials</i> , 2020 , 32, 8120-8128	9.6	3
492	Al ₂ O ₃ Thin Films Prepared by a Combined Thermal-Plasma Atomic Layer Deposition Process at Low Temperature for Encapsulation Applications. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2020 , 217, 1900237	1.6	2

491	Preparation and in vivo evaluation of red blood cell membrane coated porous silicon nanoparticles implanted with Tb. <i>Nuclear Medicine and Biology</i> , 2020 , 84-85, 102-110	2.1	4
490	Charge carrier dynamics in tantalum oxide overlayers and tantalum doped hematite photoanodes. <i>Journal of Materials Chemistry A</i> , 2019 , 7, 3206-3215	13	15
489	Titania Nanotubes/Hydroxyapatite Nanocomposites Produced with the Use of the Atomic Layer Deposition Technique: Estimation of Bioactivity and Nanomechanical Properties. <i>Nanomaterials</i> , 2019 , 9,	5.4	13
488	Comparative study on the use of novel heteroleptic cyclopentadienyl-based zirconium precursors with H ₂ O and O ₃ for atomic layer deposition of ZrO ₂ . <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020912	2.9	2
487	Fully Automated Online Dynamic In-Tube Extraction for Continuous Sampling of Volatile Organic Compounds in Air. <i>Analytical Chemistry</i> , 2019 , 91, 8507-8515	7.8	11
486	Intercalation of Lithium Ions from Gaseous Precursors into MnO ₂ Thin Films Deposited by Atomic Layer Deposition. <i>Journal of Physical Chemistry C</i> , 2019 , 123, 15802-15814	3.8	9
485	Studies on solid state reactions of atomic layer deposited thin films of lithium carbonate with hafnia and zirconia. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020929	2.9	5
484	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl ₂ (TMPDA) and Tert-Butylhydrazine as Precursors. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2019 , 216, 1900058	1.6	4
483	Review Article: Atomic layer deposition of optoelectronic materials. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019 , 37, 030801	1.3	34
482	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020921	2.9	10
481	Electrospun sodium titanate fibres for fast and selective water purification. <i>Environmental Technology (United Kingdom)</i> , 2019 , 40, 3561-3567	2.6	2
480	Atomic Layer Deposition of Emerging 2D Semiconductors, HfS ₂ and ZrS ₂ , for Optoelectronics. <i>Chemistry of Materials</i> , 2019 , 31, 5713-5724	9.6	36
479	Submicron fibers as a morphological improvement of amorphous zirconium oxide particles and their utilization in antimonate (Sb(v)) removal. <i>RSC Advances</i> , 2019 , 9, 22355-22365	3.7	6
478	Atomic Layer Deposition of Photoconductive CuO Thin Films. <i>ACS Omega</i> , 2019 , 4, 11205-11214	3.9	19
477	Nickel Germanide Thin Films by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2019 , 31, 5314-5319	9.6	5
476	Toward epitaxial ternary oxide multilayer device stacks by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020602	2.9	3
475	Low-Temperature Plasma-Enhanced Atomic Layer Deposition of SiO ₂ Using Carbon Dioxide. <i>Nanoscale Research Letters</i> , 2019 , 14, 55	5	2
474	Controlling the refractive index and third-order nonlinearity of polyimide/Ta ₂ O ₅ nanolaminates for optical applications. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 060908	2.9	4

473	Photoassisted atomic layer deposition of oxides employing alkoxides as single-source precursors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 060911	2.9	5
472	Novel electroblowing synthesis of submicron zirconium dioxide fibers: effect of fiber structure on antimony(V) adsorption. <i>Nanoscale Advances</i> , 2019 , 1, 4373-4383	5.1	9
471	Atomic layer deposition of cobalt(II) oxide thin films from Co(BTSA) ₂ (THF) and H ₂ O. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 010908	2.9	1
470	TiO Photocatalyzed Oxidation of Drugs Studied by Laser Ablation Electrospray Ionization Mass Spectrometry. <i>Journal of the American Society for Mass Spectrometry</i> , 2019 , 30, 639-646	3.5	9
469	Atomic Layer Deposition of PbI ₂ Thin Films. <i>Chemistry of Materials</i> , 2019 , 31, 1101-1109	9.6	34
468	Atomic Layer Deposition of Intermetallic Co ₃ Sn ₂ and Ni ₃ Sn ₂ Thin Films. <i>Advanced Materials Interfaces</i> , 2019 , 6, 1801291	4.6	8
467	Low-Temperature Wafer-Scale Deposition of Continuous 2D SnS Films. <i>Small</i> , 2018 , 14, e1800547	11	33
466	Zeolitic imidazole Framework-8 (ZIF-8) fibers by gas-phase conversion of electroblown zinc oxide and aluminum doped zinc oxide fibers. <i>Microporous and Mesoporous Materials</i> , 2018 , 267, 212-220	5.3	12
465	Tracing grog and pots to reveal Neolithic Corded Ware Culture contacts in the Baltic Sea region (SEM-EDS, PIXE). <i>Journal of Archaeological Science</i> , 2018 , 91, 77-91	2.9	17
464	Atomic Layer Deposition of Rhenium Disulfide. <i>Advanced Materials</i> , 2018 , 30, e1703622	24	45
463	Metal oxide multilayer hard mask system for 3D nanofabrication. <i>Nanotechnology</i> , 2018 , 29, 055301	3.4	5
462	Towards space-grade 3D-printed, ALD-coated small satellite propulsion components for fluidics. <i>Additive Manufacturing</i> , 2018 , 22, 31-37	6.1	9
461	Patterned films by atomic layer deposition using Parafilm as a mask. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 01B102	2.9	3
460	Atomic layer deposition of lanthanum oxide with heteroleptic cyclopentadienyl-amidinate lanthanum precursor - Effect of the oxygen source on the film growth and properties. <i>Thin Solid Films</i> , 2018 , 660, 199-206	2.2	7
459	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. <i>Angewandte Chemie</i> , 2018 , 130, 14746-14750	3.6	2
458	Adhesion and mechanical properties of nanocrystalline hydroxyapatite coating obtained by conversion of atomic layer-deposited calcium carbonate on titanium substrate. <i>Journal of Materials Science: Materials in Medicine</i> , 2018 , 29, 111	4.5	12
457	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. <i>Angewandte Chemie - International Edition</i> , 2018 , 57, 14538-14542	16.4	16
456	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. <i>Chemistry of Materials</i> , 2018 , 30, 3499-3507 ²¹	8.6	21

455 Electroluminescent Phosphors **2018**,

454 Metal Fluorides as Lithium-Ion Battery Materials: An Atomic Layer Deposition Perspective. *Coatings*, **2018**, 8, 277 2.9 26

453 Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. *Chemistry of Materials*, **2018**, 30, 8690-8701 9.6 16

452 Atomic Layer Deposition and Properties of HfO₂-Al₂O₃ Nanolaminates. *ECS Journal of Solid State Science and Technology*, **2018**, 7, P501-P508 2 4

451 Atomic Layer Deposition and Performance of ZrO₂-Al₂O₃ Thin Films. *ECS Journal of Solid State Science and Technology*, **2018**, 7, P287-P294 2 8

450 Atomic layer deposition of crystalline molybdenum oxide thin films and phase control by post-deposition annealing. *Materials Today Chemistry*, **2018**, 9, 17-27 6.2 22

449 Enhanced process and composition control for atomic layer deposition with lithium trimethylsilylanolate. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 01B133 2.9 11

448 Atomic layer deposition and properties of mixed Ta₂O₅ and ZrO₂ films. *AIP Advances*, **2017**, 7, 025001 1.5 21

447 Potential gold(I) precursors evaluated for atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 01B112 2.9 13

446 Surface modification of acetaminophen particles by atomic layer deposition. *International Journal of Pharmaceutics*, **2017**, 525, 160-174 6.5 31

445 Studies on Li₃AlF₆ thin film deposition utilizing conversion reactions of thin films. *Thin Solid Films*, **2017**, 636, 26-33 2.2 5

444 Atomic layer deposition of tin oxide thin films from bis[bis(trimethylsilyl)amino]tin(II) with ozone and water. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 041506 2.9 12

443 Atomic Layer Deposition of Crystalline MoS₂ Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. *Advanced Materials Interfaces*, **2017**, 4, 1700123 4.6 75

442 As₂S₃ thin films deposited by atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2017**, 35, 01B114 2.9 8

441 TiO Photocatalysis-DESI-MS Rotating Array Platform for High-Throughput Investigation of Oxidation Reactions. *Analytical Chemistry*, **2017**, 89, 11214-11218 7.8 5

440 Atomic Layer Deposition of Zinc Glutarate Thin Films. *Advanced Materials Interfaces*, **2017**, 4, 1700512 4.6 2

439 Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. *Chemistry of Materials*, **2017**, 29, 5796-5805 9.6 32

438 Atomic Layer Deposited Protective Layers. *Materials Science Forum*, **2016**, 879, 1086-1092 0.4 2

437	Rapid production of bioactive hydroxyapatite fibers via electroblowing. <i>Journal of the European Ceramic Society</i> , 2016 , 36, 3219-3224	6	22
436	Nuclear reaction analysis for H, Li, Be, B, C, N, O and F with an RBS check. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2016 , 371, 211-215	1.2	28
435	Bismuth iron oxide thin films using atomic layer deposition of alternating bismuth oxide and iron oxide layers. <i>Thin Solid Films</i> , 2016 , 611, 78-87	2.2	16
434	Atomic layer deposition of aluminum oxide on modified steel substrates. <i>Surface and Coatings Technology</i> , 2016 , 304, 1-8	4.4	10
433	Electric and Magnetic Properties of ALD-Grown BiFeO ₃ Films. <i>Journal of Physical Chemistry C</i> , 2016 , 120, 7313-7322	3.8	25
432	Interfacial native oxide effects on the corrosion protection of copper coated with ALD alumina. <i>Electrochimica Acta</i> , 2016 , 193, 7-15	6.7	19
431	Corrosion protection of aluminium by ultra-thin atomic layer deposited alumina coatings. <i>Corrosion Science</i> , 2016 , 106, 16-24	6.8	50
430	Alkylsilyl compounds as enablers of atomic layer deposition: analysis of (Et ₃ Si) ₃ As through the GaAs process. <i>Journal of Materials Chemistry C</i> , 2016 , 4, 449-454	7.1	2
429	Structure-Dependent Mechanical Properties of ALD-Grown Nanocrystalline BiFeO ₃ Multiferroics. <i>Journal of Nanomaterials</i> , 2016 , 2016, 1-7	3.2	5
428	The role of surface preparation in corrosion protection of copper with nanometer-thick ALD alumina coatings. <i>Applied Surface Science</i> , 2016 , 387, 1054-1061	6.7	20
427	Heteroleptic Cyclopentadienyl-Amidinate Precursors for Atomic Layer Deposition (ALD) of Y, Pr, Gd, and Dy Oxide Thin Films. <i>Chemistry of Materials</i> , 2016 , 28, 5440-5449	9.6	23
426	Atomic Layer Deposition of Iridium Thin Films Using Sequential Oxygen and Hydrogen Pulses. <i>Journal of Physical Chemistry C</i> , 2016 , 120, 15235-15243	3.8	23
425	Low-temperature atomic layer deposition of copper(II) oxide thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 01A109	2.9	18
424	Scalable Route to the Fabrication of CH ₃ NH ₃ PbI Perovskite Thin Films by Electrodeposition and Vapor Conversion. <i>ACS Omega</i> , 2016 , 1, 1296-1306	3.9	32
423	Atomic Layer Deposition (ALD) grown thin films for ultra-fine pitch pixel detectors. <i>Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment</i> , 2016 , 831, 2-6	1.2	7
422	MANOS performance dependence on ALD Al ₂ O ₃ oxidation source. <i>Microelectronic Engineering</i> , 2016 , 159, 127-131	2.5	1
421	Nucleation and Conformality of Iridium and Iridium Oxide Thin Films Grown by Atomic Layer Deposition. <i>Langmuir</i> , 2016 , 32, 10559-10569	4	24
420	Coating and functionalization of high density ion track structures by atomic layer deposition. <i>Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment</i> , 2016 , 832, 254-258	1.2	1

4 ¹⁹	Selective etching of focused gallium ion beam implanted regions from silicon as a nanofabrication method. <i>Nanotechnology</i> , 2015 , 26, 265304	3.4	5
4 ¹⁸	Atomic layer deposition of zirconium dioxide from zirconium tetrachloride and ozone. <i>Thin Solid Films</i> , 2015 , 589, 597-604	2.2	18
4 ¹⁷	Inert ambient annealing effect on MANOS capacitor memory characteristics. <i>Nanotechnology</i> , 2015 , 26, 134004	3.4	15
4 ¹⁶	Following the dynamics of matter with femtosecond precision using the X-ray streaking method. <i>Scientific Reports</i> , 2015 , 5, 7644	4.9	23
4 ¹⁵	Osteogenic and osteoclastogenic differentiation of co-cultured cells in polylactic acid-nanohydroxyapatite fiber scaffolds. <i>Journal of Biotechnology</i> , 2015 , 204, 53-62	3.7	44
4 ¹⁴	(Et ₃ Si) ₂ Se as a precursor for atomic layer deposition: growth analysis of thermoelectric Bi ₂ Se ₃ . <i>Journal of Materials Chemistry C</i> , 2015 , 3, 4820-4828	7.1	12
4 ¹³	Nitrogen induced modifications of MANOS memory properties. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2015 , 365, 61-65	1.2	1
4 ¹²	High Aspect-Ratio Iridium-Coated Nanopillars for Highly Reproducible Surface-Enhanced Raman Scattering (SERS). <i>ACS Applied Materials & Interfaces</i> , 2015 , 7, 11452-9	9.5	24
4 ¹¹	High resolution double-sided diffractive optics for hard X-ray microscopy. <i>Optics Express</i> , 2015 , 23, 776-863	8.3	41
4 ¹⁰	Slot waveguide ring resonators coated by an atomic layer deposited organic/inorganic nanolaminate. <i>Optics Express</i> , 2015 , 23, 26940-51	3.3	11
4 ⁰⁹	Conduction and stability of holmium titanium oxide thin films grown by atomic layer deposition. <i>Thin Solid Films</i> , 2015 , 591, 55-59	2.2	1
4 ⁰⁸	Mechanical properties of aluminum, zirconium, hafnium and tantalum oxides and their nanolaminates grown by atomic layer deposition. <i>Surface and Coatings Technology</i> , 2015 , 282, 36-42	4.4	24
4 ⁰⁷	Electrochemical and Surface Analysis of the Corrosion Protection of Copper by Nanometer-Thick Alumina Coatings Prepared by Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2015 , 162, C377-C384	3.9	17
4 ⁰⁶	MANOS erase performance dependence on nitrogen annealing conditions. <i>Materials Research Society Symposia Proceedings</i> , 2015 , 1729, 15-20		
4 ⁰⁵	Osteoclasts in the interface with electrospun hydroxyapatite. <i>Colloids and Surfaces B: Biointerfaces</i> , 2015 , 135, 774-783	6	13
4 ⁰⁴	Needleless electrospinning with twisted wire spinneret. <i>Nanotechnology</i> , 2015 , 26, 025301	3.4	52
4 ⁰³	Atomic layer deposition and characterization of Bi ₂ Te ₃ thin films. <i>Journal of Physical Chemistry A</i> , 2015 , 119, 2298-306	2.8	23
4 ⁰²	Studies on atomic layer deposition of IRMOF-8 thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 01A121	2.9	17

401	Impedance spectroscopy study of the unipolar and bipolar resistive switching states of atomic layer deposited polycrystalline ZrO ₂ thin films. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2015 , 212, 751-766	1.6	18
400	Atomic Layer Deposition of AlF ₃ Thin Films Using Halide Precursors. <i>Chemistry of Materials</i> , 2015 , 27, 604-611	9.6	27
399	X-ray ptychographic computed tomography at 16 nm isotropic 3D resolution. <i>Scientific Reports</i> , 2014 , 4, 3857	4.9	228
398	In situ reaction mechanism studies on the Ti(NMe ₂) ₂ (OiPr) ₂ -D ₂ O and Ti(OiPr) ₃ [MeC(NiPr) ₂]-D ₂ O atomic layer deposition processes. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014 , 32, 01A121	2.9	1
397	Voltage-Dependent Properties of Titanium Dioxide Nanotubes Anodized in Solutions Containing EDTA. <i>Journal of the Electrochemical Society</i> , 2014 , 161, E61-E65	3.9	4
396	Atomic Layer Deposition of Noble Metals and Their Oxides. <i>Chemistry of Materials</i> , 2014 , 26, 786-801	9.6	244
395	Single-parameter model for the post-breakdown conduction characteristics of HoTiO _x -based MIM capacitors. <i>Microelectronics Reliability</i> , 2014 , 54, 1707-1711	1.2	
394	Combining focused ion beam and atomic layer deposition in nanostructure fabrication. <i>Nanotechnology</i> , 2014 , 25, 115302	3.4	2
393	Electrospinning of calcium carbonate fibers and their conversion to nanocrystalline hydroxyapatite. <i>Materials Science and Engineering C</i> , 2014 , 45, 469-76	8.3	11
392	Holmium and titanium oxide nanolaminates by atomic layer deposition. <i>Thin Solid Films</i> , 2014 , 565, 165-171	17.1	9
391	Preparation and bioactive properties of nanocrystalline hydroxyapatite thin films obtained by conversion of atomic layer deposited calcium carbonate. <i>Biointerphases</i> , 2014 , 9, 031008	1.8	11
390	Heteroleptic Precursors for Atomic Layer Deposition. <i>ECS Transactions</i> , 2014 , 64, 221-232	1	3
389	Atomic Layer Deposition of TiO ₂ and ZrO ₂ Thin Films Using Heteroleptic Guanidinate Precursors. <i>Chemical Vapor Deposition</i> , 2014 , 20, 209-216		5
388	Interface control of atomic layer deposited oxide coatings by filtered cathodic arc deposited sublayers for improved corrosion protection. <i>Materials Chemistry and Physics</i> , 2014 , 147, 895-907	4.4	8
387	Modification of Hematite Electronic Properties with Trimethyl Aluminum to Enhance the Efficiency of Photoelectrodes. <i>Journal of Physical Chemistry Letters</i> , 2014 , 5, 3582-7	6.4	21
386	Sealing of hard CrN and DLC coatings with atomic layer deposition. <i>ACS Applied Materials & Interfaces</i> , 2014 , 6, 1893-901	9.5	45
385	Corrosion properties of steel protected by nanometre-thick oxide coatings. <i>Corrosion Science</i> , 2014 , 82, 208-217	6.8	25
384	Atomic layer deposition, characterization, and growth mechanistic studies of TiO ₂ thin films. <i>Langmuir</i> , 2014 , 30, 7395-404	4	12

- 383 Holmium titanium oxide thin films grown by atomic layer deposition. *Thin Solid Films*, **2014**, 565, 261-266.2 10
- 382 Study of atomic layer deposited ZrO₂ and ZrO₂/TiO₂ films for resistive switching application. *Physica Status Solidi (A) Applications and Materials Science*, **2014**, 211, 301-309 1.6 13
- 381 Atomic Layer Deposition **2014**, 101-123 27
- 380 PCRAM **2014**, 123-148
- 379 Magnetic Properties of Polycrystalline Bismuth Ferrite Thin Films Grown by Atomic Layer Deposition. *Journal of Physical Chemistry Letters*, **2014**, 5, 4319-23 6.4 21
- 378 Cyclopentadienyl Precursors for the Atomic Layer Deposition of Erbium Oxide Thin Films. *Chemical Vapor Deposition*, **2014**, 20, 217-223 7
- 377 Atomic-scale engineering of multifunctional nano-sized materials and films. *Physica Status Solidi (A) Applications and Materials Science*, **2014**, 211, 249-250 1.6
- 376 Atomic Layer Deposition of Groups 4 and 5 Transition Metal Oxide Thin Films: Focus on Heteroleptic Precursors. *Chemical Vapor Deposition*, **2014**, 20, 189-208 22
- 375 Resistive Switching Behavior and Electrical Properties of TiO₂:Ho₂O₃ and HoTiO_x Based MIM Capacitors. *Materials Research Society Symposia Proceedings*, **2014**, 1691, 43 1
- 374 Continuous-Wave Laser Annealing of a Si/SiO₂ Superlattice: Effect of the Ambient Atmosphere and Exposure Period. *Science of Advanced Materials*, **2014**, 6, 1000-1010 2.3 3
- 373 In Situ Studies on Reaction Mechanisms in Atomic Layer Deposition. *Critical Reviews in Solid State and Materials Sciences*, **2013**, 38, 167-202 10.1 76
- 372 Al_xTa_yO_z Mixture Coatings Prepared Using Atomic Layer Deposition for Corrosion Protection of Steel. *Chemical Vapor Deposition*, **2013**, 19, 194-203 13
- 371 Tantalum oxide nanocoatings prepared by atomic layer and filtered cathodic arc deposition for corrosion protection of steel: Comparative surface and electrochemical analysis. *Electrochimica Acta*, **2013**, 90, 232-245 6.7 71
- 370 Changes in the cross-country ski base properties resulting from the ski use. *Sports Engineering*, **2013**, 16, 229-238 1.4 2
- 369 Studies on atomic layer deposition of MOF-5 thin films. *Microporous and Mesoporous Materials*, **2013**, 182, 147-154 5.3 58
- 368 History of atomic layer deposition and its relationship with the American Vacuum Society. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2013**, 31, 050818 2.9 73
- 367 Atomic layer deposition and characterization of vanadium oxide thin films. *RSC Advances*, **2013**, 3, 1179-1185 65
- 366 Precursors as enablers of ALD technology: Contributions from University of Helsinki. *Coordination Chemistry Reviews*, **2013**, 257, 3297-3322 23.2 63

365	Hydrogen/Argon plasma pre-treatment for improving the anti-corrosion properties of thin Al ₂ O ₃ films deposited using atomic layer deposition on steel. <i>Thin Solid Films</i> , 2013 , 534, 384-393	2.2	23
364	Stopping cross sections of atomic layer deposited Al ₂ O ₃ and Ta ₂ O ₅ and of Si ₃ N ₄ for ¹² C, ¹⁶ O, ³⁵ Cl, ⁷⁹ Br and ¹²⁷ I ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2013 , 300, 1-5	1.2	5
363	The effect of oxygen source on atomic layer deposited Al ₂ O ₃ as blocking oxide in metal/aluminum oxide/nitride/oxide/silicon memory capacitors. <i>Thin Solid Films</i> , 2013 , 533, 5-8	2.2	8
362	Crystallinity of inorganic films grown by atomic layer deposition: Overview and general trends. <i>Journal of Applied Physics</i> , 2013 , 113, 021301	2.5	1011
361	Structural and Magnetic Studies on Iron Oxide and Iron-Magnesium Oxide Thin Films Deposited Using Ferrocene and (Dimethylaminomethyl)ferrocene Precursors. <i>ECS Journal of Solid State Science and Technology</i> , 2013 , 2, N45-N54	2	21
360	Photocatalytic Properties of WO ₃ /TiO ₂ Core/Shell Nanofibers prepared by Electrospinning and Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 2013 , 19, 149-155		58
359	Low temperature atomic layer deposition of noble metals using ozone and molecular hydrogen as reactants. <i>Thin Solid Films</i> , 2013 , 531, 243-250	2.2	38
358	In Situ Reaction Mechanism Studies on Lithium Hexadimethyldisilazide and Ozone Atomic Layer Deposition Process for Lithium Silicate. <i>Journal of Physical Chemistry C</i> , 2013 , 117, 14241-14246	3.8	20
357	Atomic Layer Deposition of LiF Thin Films from Lithd, Mg(thd) ₂ , and TiF ₄ Precursors. <i>Chemistry of Materials</i> , 2013 , 25, 1656-1663	9.6	33
356	Deposition of Copper by Plasma-Enhanced Atomic Layer Deposition Using a Novel N-Heterocyclic Carbene Precursor. <i>Chemistry of Materials</i> , 2013 , 25, 1132-1138	9.6	39
355	[Zr(NEtMe) ₂ (guan-NEtMe) ₂] as a Novel Atomic Layer Deposition Precursor: ZrO ₂ Film Growth and Mechanistic Studies. <i>Chemistry of Materials</i> , 2013 , 25, 3088-3095	9.6	16
354	Programming nanostructured soft biological surfaces by atomic layer deposition. <i>Nanotechnology</i> , 2013 , 24, 245701	3.4	25
353	Influence of growth and annealing temperatures on the electrical properties of Nb ₂ O ₅ -based MIM capacitors. <i>Semiconductor Science and Technology</i> , 2013 , 28, 055005	1.8	10
352	Atomic Layer Deposition of LiF Thin Films from Lithd and TiF ₄ Precursors. <i>Chemical Vapor Deposition</i> , 2013 , 19, 111-116		28
351	Influence of atomic layer deposition chemistry on high-k dielectrics for charge trapping memories. <i>Solid-State Electronics</i> , 2012 , 68, 38-47	1.7	14
350	Atomic layer deposition of Ru films from bis(2,5-dimethylpyrrolyl)ruthenium and oxygen. <i>Thin Solid Films</i> , 2012 , 520, 2756-2763	2.2	24
349	Optical and Dielectric Characterization of Atomic Layer Deposited Nb ₂ O ₅ Thin Films. <i>ECS Solid State Letters</i> , 2012 , 1, N1-N3		12
348	In Situ Reaction Mechanism Studies on the New tBuN=M(NEt ₂) ₃ -Water and tBuN=M(NEt ₂) ₃ - Ozone (M = Nb,Ta) Atomic Layer Deposition Processes. <i>Chemistry of Materials</i> , 2012 , 24, 1555-1561	9.6	13

347	Atomic Layer Deposition of Osmium. <i>Chemistry of Materials</i> , 2012 , 24, 55-60	9.6	33
346	Microcontact Printed RuOx Film as an Activation Layer for Selective-Area Atomic Layer Deposition of Ruthenium. <i>Chemistry of Materials</i> , 2012 , 24, 275-278	9.6	37
345	Evaluation and Comparison of Novel Precursors for Atomic Layer Deposition of Nb2O5 Thin Films. <i>Chemistry of Materials</i> , 2012 , 24, 975-980	9.6	41
344	Surface chemistry, reactivity, and pore structure of porous silicon oxidized by various methods. <i>Langmuir</i> , 2012 , 28, 10573-83	4	70
343	In Situ Reaction Mechanism Studies on Atomic Layer Deposition of AlxSiyOz from Trimethylaluminium, Hexakis(ethylamino)disilane, and Water. <i>Chemistry of Materials</i> , 2012 , 24, 3859-3867	9.6	16
342	Atomic Layer Deposition of Aluminum and Titanium Phosphates. <i>Journal of Physical Chemistry C</i> , 2012 , 116, 5920-5925	3.8	31
341	Cycloheptatrienyl-Cyclopentadienyl Heteroleptic Precursors for Atomic Layer Deposition of Group 4 Oxide Thin Films. <i>Chemistry of Materials</i> , 2012 , 24, 2002-2008	9.6	22
340	Passivation of copper surfaces for selective-area ALD using a thiol self-assembled monolayer. <i>Semiconductor Science and Technology</i> , 2012 , 27, 074004	1.8	40
339	Novel Heteroleptic Precursors for Atomic Layer Deposition of TiO2. <i>Chemistry of Materials</i> , 2012 , 24, 3420-3424	9.6	23
338	Double metal alkoxides of lithium: Synthesis, structure and applications in materials chemistry. <i>Coordination Chemistry Reviews</i> , 2012 , 256, 854-877	23.2	23
337	Surface fingerprints of individual silicon nanocrystals in laser-annealed Si/SiO2 superlattice: Evidence of nanoeruptions of laser-pressurized silicon. <i>Journal of Applied Physics</i> , 2012 , 111, 124302	2.5	3
336	Conformality of remote plasma-enhanced atomic layer deposition processes: An experimental study. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A115	2.9	48
335	Study of amorphous lithium silicate thin films grown by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A106	2.9	35
334	Lithium Phosphate Thin Films Grown by Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2012 , 159, A259-A263	3.9	77
333	Spoof-like plasmonic behavior of plasma enhanced atomic layer deposition grown Ag thin films. <i>Applied Physics Letters</i> , 2012 , 100, 053106	3.4	17
332	High-performance imido-imido precursor for the atomic layer deposition of Ta2O5. <i>Semiconductor Science and Technology</i> , 2012 , 27, 074003	1.8	12
331	Preparation of regularly structured nanotubular TiO2 thin films on ITO and their modification with thin ALD-grown layers. <i>Nanotechnology</i> , 2012 , 23, 125707	3.4	21
330	Plasma-Enhanced Atomic Layer Deposition of Silver Thin Films. <i>Chemistry of Materials</i> , 2011 , 23, 2901-2907	9.7	89

329	Substrate Reactivity Effects in the Atomic Layer Deposition of Aluminum Oxide from Trimethylaluminum on Ruthenium. <i>Chemistry of Materials</i> , 2011 , 23, 3159-3168	9.6	28
328	Iridium metal and iridium oxide thin films grown by atomic layer deposition at low temperatures. <i>Journal of Materials Chemistry</i> , 2011 , 21, 16488		39
327	In situ Reaction Mechanism Studies on Atomic Layer Deposition of Ir and IrO ₂ from Ir(acac) ₃ . <i>Chemistry of Materials</i> , 2011 , 23, 2766-2771	9.6	34
326	Nanofocusing of hard X-ray free electron laser pulses using diamond based Fresnel zone plates. <i>Scientific Reports</i> , 2011 , 1, 57	4.9	108
325	Low-temperature atomic layer deposition of Al ₂ O ₃ thin coatings for corrosion protection of steel: Surface and electrochemical analysis. <i>Corrosion Science</i> , 2011 , 53, 2168-2175	6.8	162
324	Ultra-high resolution zone-doubled diffractive X-ray optics for the multi-keV regime. <i>Optics Express</i> , 2011 , 19, 175-84	3.3	102
323	Large-area plasmonic hot-spot arrays: sub-2 nm interparticle separations with plasma-enhanced atomic layer deposition of Ag on periodic arrays of Si nanopillars. <i>Optics Express</i> , 2011 , 19, 26056-64	3.3	46
322	Thermal study on electrospun polyvinylpyrrolidone/ammonium metatungstate nanofibers: optimising the annealing conditions for obtaining WO ₃ nanofibers. <i>Journal of Thermal Analysis and Calorimetry</i> , 2011 , 105, 73-81	4.1	79
321	Zone-Doubled Fresnel Zone Plates for Scanning Transmission X-ray Microscopy 2011 ,		2
320	Electrochemical and time-of-flight secondary ion mass spectrometry analysis of ultra-thin metal oxide (Al ₂ O ₃ and Ta ₂ O ₅) coatings deposited by atomic layer deposition on stainless steel. <i>Electrochimica Acta</i> , 2011 , 56, 10516-10523	6.7	63
319	Failure mechanism of thin Al ₂ O ₃ coatings grown by atomic layer deposition for corrosion protection of carbon steel. <i>Electrochimica Acta</i> , 2011 , 56, 9609-9618	6.7	50
318	Crystal structures and thermal properties of some rare earth alkoxides with tertiary alcohols. <i>Journal of Thermal Analysis and Calorimetry</i> , 2011 , 105, 61-71	4.1	5
317	Photoswitchable Superabsorbency Based on Nanocellulose Aerogels. <i>Advanced Functional Materials</i> , 2011 , 21, 510-517	15.6	218
316	Integrated photocatalytic micropillar nanoreactor electro spray ionization chip for mimicking phase I metabolic reactions. <i>Lab on A Chip</i> , 2011 , 11, 1470-6	7.2	23
315	Chemical vapour deposition of In ₂ O ₃ thin films from a tris-guanidinate indium precursor. <i>Dalton Transactions</i> , 2011 , 40, 9425-30	4.3	21
314	Novel materials by atomic layer deposition and molecular layer deposition. <i>MRS Bulletin</i> , 2011 , 36, 877-884		41
313	Atomic Layer Deposition of Antimony and its Compounds Using Dechlorosilylation Reactions of Tris(triethylsilyl)antimony. <i>Chemistry of Materials</i> , 2011 , 23, 247-254	9.6	40
312	Atomic layer deposition of ferromagnetic cobalt doped titanium oxide thin films. <i>Thin Solid Films</i> , 2011 , 519, 3318-3324	2.2	14

311	Surface Enhanced Raman Scattering Enhancements from Silver Atomic Layer Deposition Coated Nanowire 2011 ,		1
310	Atomic layer deposition of ruthenium films on strontium titanate. <i>Journal of Nanoscience and Nanotechnology</i> , 2011 , 11, 8378-82	1.3	1
309	Influence of precursor chemistry and growth temperature on the electrical properties of SrTiO ₃ -based metal-insulator-metal capacitors grown by atomic layer deposition. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2011 , 29, 01AC04	1.3	7
308	Atomic Layer Deposition of Ruthenium Films from (Ethylcyclopentadienyl)(pyrrolyl)ruthenium and Oxygen. <i>Journal of the Electrochemical Society</i> , 2011 , 158, D158	3.9	48
307	Influence of HfO ₂ Control Oxide ALD Precursor Chemistry for Nitride Memories. <i>Advanced Materials Research</i> , 2011 , 324, 42-45	0.5	1
306	Atomic Layer Deposition and Characterization of Aluminum Silicate Thin Films for Optical Applications. <i>Journal of the Electrochemical Society</i> , 2011 , 158, P15	3.9	13
305	Atomic Layer Deposition and Characterization of GeTe Thin Films. <i>Journal of the Electrochemical Society</i> , 2011 , 158, D694	3.9	23
304	Corrosion Protection of Steel with Oxide Nanolaminates Grown by Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2011 , 158, C369	3.9	51
303	Investigation of ZrO ₂ /Cd ₂ O ₃ Based High-k Materials as Capacitor Dielectrics. <i>Journal of the Electrochemical Society</i> , 2010 , 157, G202	3.9	15
302	Charge trapping memories with atomic layer deposited high-k dielectrics capping layers. <i>Materials Research Society Symposia Proceedings</i> , 2010 , 1250, 1		
301	High Temperature Atomic Layer Deposition of Ruthenium from N,N-Dimethyl-1-ruthenocenyethylamine. <i>Journal of the Electrochemical Society</i> , 2010 , 157, D35	3.9	29
300	Atomic Layer Deposition and Characterization of Erbium Oxide-Doped Zirconium Oxide Thin Films. <i>Journal of the Electrochemical Society</i> , 2010 , 157, G193	3.9	10
299	2010 ,		3
298	High Spatial Resolution STXM at 6.2 keV Photon Energy 2010 ,		3
297	Fabrication of nanocluster silicon surface with electric discharge and the application in desorption/ionization on silicon-mass spectrometry. <i>Lab on A Chip</i> , 2010 , 10, 1689-95	7.2	
296	(MeCp)Ir(CHD) and molecular oxygen as precursors in atomic layer deposition of iridium. <i>Journal of Materials Chemistry</i> , 2010 , 20, 7669		32
295	In situ reaction mechanism studies on ozone-based atomic layer deposition of Al ₂ O ₃ and HfO ₂ . <i>ACS Applied Materials & Interfaces</i> , 2010 , 2, 347-50	9.5	40
294	Molecular organization of the tear fluid lipid layer. <i>Biophysical Journal</i> , 2010 , 99, 2559-67	2.9	59

293	In Situ Reaction Mechanism Studies on Atomic Layer Deposition of Sb ₂ Te ₃ and GeTe from (Et ₃ Si) ₂ Te and Chlorides. <i>Chemistry of Materials</i> , 2010 , 22, 1386-1391	9.6	46
292	Dense high aspect ratio hydrogen silsesquioxane nanostructures by 100 keV electron beam lithography. <i>Nanotechnology</i> , 2010 , 21, 285305	3.4	41
291	Reaction mechanism studies on atomic layer deposition of Nb ₂ O ₅ from Nb(OEt) ₅ and water. <i>Langmuir</i> , 2010 , 26, 848-53	4	14
290	Study of bismuth alkoxides as possible precursors for ALD. <i>Dalton Transactions</i> , 2010 , 39, 3219-26	4.3	37
289	Rare earth scandate thin films by atomic layer deposition: effect of the rare earth cation size. <i>Journal of Materials Chemistry</i> , 2010 , 20, 4207		29
288	Selective-Area Atomic Layer Deposition Using Poly(vinyl pyrrolidone) as a Passivation Layer. <i>Journal of the Electrochemical Society</i> , 2010 , 157, K10	3.9	57
287	Electroactivity and biocompatibility of polypyrrole-hyaluronic acid multi-walled carbon nanotube composite. <i>Journal of Biomedical Materials Research - Part A</i> , 2010 , 93, 1056-67	5.4	4
286	Properties of HfO ₂ and HfO ₂ :Y films grown by atomic layer deposition in an advanced monocyclopentadienyl-based process. <i>IOP Conference Series: Materials Science and Engineering</i> , 2010 , 8, 012022	0.4	2
285	Ta ₂ O ₅ - and TiO ₂ -based nanostructures made by atomic layer deposition. <i>Nanotechnology</i> , 2010 , 21, 035301	3.4	16
284	Silver coated platinum core-shell nanostructures on etched Si nanowires: atomic layer deposition (ALD) processing and application in SERS. <i>ChemPhysChem</i> , 2010 , 11, 1995-2000	3.2	5
283	Liposomes for entrapping local anesthetics: a liposome electrokinetic chromatographic study. <i>Electrophoresis</i> , 2010 , 31, 1540-9	3.6	17
282	Growth and phase stabilization of HfO ₂ thin films by ALD using novel precursors. <i>Journal of Crystal Growth</i> , 2010 , 312, 245-249	1.6	53
281	Structure and morphology of Ru films grown by atomic layer deposition from 1-ethyl-1-methyl-ruthenocene. <i>Journal of Crystal Growth</i> , 2010 , 312, 2025-2032	1.6	21
280	Atomic layer deposition of high capacitance density Ta ₂ O ₅ /rO ₂ based dielectrics for metal/insulator/metal structures. <i>Microelectronic Engineering</i> , 2010 , 87, 144-149	2.5	30
279	Atomic layer deposition and characterization of zirconium oxide/erbium oxide nanolaminates. <i>Thin Solid Films</i> , 2010 , 519, 666-673	2.2	12
278	Beam-induced damage on diffractive hard X-ray optics. <i>Journal of Synchrotron Radiation</i> , 2010 , 17, 786-90.4	0.4	7
277	Atomic Layer Deposition of High-Permittivity Yttrium-Doped HfO ₂ Films. <i>Electrochemical and Solid-State Letters</i> , 2009 , 12, G1		27
276	Advanced X-ray diffractive optics. <i>Journal of Physics: Conference Series</i> , 2009 , 186, 012078	0.3	7

275	Novel Zirconium Precursors for Atomic Layer Deposition of ZrO ₂ Films. <i>ECS Transactions</i> , 2009 , 16, 87-101		5
274	Behavior of zirconium oxide films processed from novel monocyclopentadienyl precursors by atomic layer deposition. <i>Journal of Vacuum Science & Technology B</i> , 2009 , 27, 226		16
273	Irradiation effect on dielectric properties of hafnium and gadolinium oxide gate dielectrics. <i>Journal of Vacuum Science & Technology B</i> , 2009 , 27, 416		17
272	Electrical properties of thin zirconium and hafnium oxide high-k gate dielectrics grown by atomic layer deposition from cyclopentadienyl and ozone precursors. <i>Journal of Vacuum Science & Technology B</i> , 2009 , 27, 389		14
271	Metallic Ir, IrO ₂ and Pt Nanotubes and Fibers by Electrospinning and Atomic Layer Deposition. <i>Nanoscience and Nanotechnology Letters</i> , 2009 , 1, 218-223	0.8	7
270	Atomic Layer Deposition of Materials for Phase-Change Memories. <i>ECS Transactions</i> , 2009 , 25, 399-407	1	17
269	Atomic Layer Deposition of High-k Oxides of the Group 4 Metals for Memory Applications. <i>Advanced Engineering Materials</i> , 2009 , 11, 223-234	3.5	105
268	ALD of YF ₃ Thin Films from TiF ₄ and Y(thd) ₃ Precursors. <i>Chemical Vapor Deposition</i> , 2009 , 15, 27-32		23
267	Atomic Layer Deposition of Ta ₂ O ₅ /Polyimide Nanolaminates. <i>Chemical Vapor Deposition</i> , 2009 , 15, 221-226		30
266	Etching of Nb ₂ O ₅ Thin Films by NbCl ₅ . <i>Chemical Vapor Deposition</i> , 2009 , 15, NA-NA		8
265	Advanced thin film technology for ultrahigh resolution X-ray microscopy. <i>Ultramicroscopy</i> , 2009 , 109, 1360-4	3.1	99
264	Phosphopeptide enrichment with stable spatial coordination on a titanium dioxide coated glass slide. <i>Rapid Communications in Mass Spectrometry</i> , 2009 , 23, 3661-7	2.2	3
263	Atomic layer deposition of Ge ₂ Sb ₂ Te ₅ thin films. <i>Microelectronic Engineering</i> , 2009 , 86, 1946-1949	2.5	58
262	Comparison between the electrical properties of atomic layer deposited thin ZrO ₂ films processed from cyclopentadienyl precursors. <i>Microelectronic Engineering</i> , 2009 , 86, 1689-1691	2.5	8
261	Effect of thickness of ALD grown TiO ₂ films on photoelectrocatalysis. <i>Journal of Photochemistry and Photobiology A: Chemistry</i> , 2009 , 204, 200-208	4.7	58
260	Atomic layer deposition of metal tellurides and selenides using alkylsilyl compounds of tellurium and selenium. <i>Journal of the American Chemical Society</i> , 2009 , 131, 3478-80	16.4	132
259	A Novel Method of Quantifying the u-Shaped Pores in SBA-15. <i>Journal of Physical Chemistry C</i> , 2009 , 113, 20349-20354	3.8	10
258	Atomic Layer Deposition of Iridium Thin Films by Consecutive Oxidation and Reduction Steps. <i>Chemistry of Materials</i> , 2009 , 21, 4868-4872	9.6	44

257	The preparation of reusable magnetic and photocatalytic composite nanofibers by electrospinning and atomic layer deposition. <i>Nanotechnology</i> , 2009 , 20, 035602	3.4	67
256	Explosive Crystallization in Atomic Layer Deposited Mixed Titanium Oxides. <i>Crystal Growth and Design</i> , 2009 , 9, 2974-2978	3.5	36
255	Industrial Applications of Atomic Layer Deposition. <i>ECS Transactions</i> , 2009 , 25, 641-652	1	93
254	Study on Atomic Layer Deposition of Amorphous Rhodium Oxide Thin Films. <i>Journal of the Electrochemical Society</i> , 2009 , 156, D418	3.9	19
253	Alkylsilyl Compounds of Selenium and Tellurium: New Precursors for ALD. <i>ECS Transactions</i> , 2009 , 25, 609-616	1	13
252	Selective-Area Atomic Layer Deposition Using Poly(methyl methacrylate) Films as Mask Layers. <i>Journal of Physical Chemistry C</i> , 2008 , 112, 15791-15795	3.8	87
251	Atomic Layer Deposition of MgF ₂ Thin Films Using TaF ₅ as a Novel Fluorine Source. <i>Chemistry of Materials</i> , 2008 , 20, 5023-5028	9.6	38
250	In Situ Reaction Mechanism Studies on Atomic Layer Deposition of ZrO ₂ from (CpMe) ₂ Zr(OMe)Me and Water or Ozone. <i>Chemistry of Materials</i> , 2008 , 20, 5698-5705	9.6	49
249	Atomic Layer Deposition of Iridium Oxide Thin Films from Ir(acac) ₃ and Ozone. <i>Chemistry of Materials</i> , 2008 , 20, 2903-2907	9.6	53
248	Identification of spatial localization and energetic position of electrically active defects in amorphous high-k dielectrics for advanced devices. <i>Journal of Non-Crystalline Solids</i> , 2008 , 354, 393-398	3.9	5
247	Selection of post-growth treatment parameters for atomic layer deposition of structurally disordered TiO ₂ thin films. <i>Journal of Non-Crystalline Solids</i> , 2008 , 354, 404-408	3.9	5
246	Atomic layer deposition process with TiF ₄ as a precursor for depositing metal fluoride thin films. <i>Applied Optics</i> , 2008 , 47, C271-4	1.7	31
245	Advanced cyclopentadienyl precursors for atomic layer deposition of ZrO ₂ thin films. <i>Journal of Materials Chemistry</i> , 2008 , 18, 3385		35
244	Atomic layer deposition of photocatalytic TiO ₂ thin films from TiF ₄ and H ₂ O. <i>Dalton Transactions</i> , 2008 , 6467-74	4.3	31
243	Novel mixed alkylamido-cyclopentadienyl precursors for ALD of ZrO ₂ thin films. <i>Journal of Materials Chemistry</i> , 2008 , 18, 5243		56
242	Atomic Layer Deposition of Platinum Oxide and Metallic Platinum Thin Films from Pt(acac) ₂ and Ozone. <i>Chemistry of Materials</i> , 2008 , 20, 6840-6846	9.6	83
241	DIELECTRIC PROPERTIES OF ATOMIC LAYER DEPOSITED THIN-FILM BARIUM STRONTIUM TITANATE. <i>Integrated Ferroelectrics</i> , 2008 , 102, 29-36	0.8	9
240	Comparative Study of Flatband Voltage Transients on High-k Dielectric-Based Metal/Insulator/Semiconductor Capacitors. <i>Journal of the Electrochemical Society</i> , 2008 , 155, G241	3.9	4

239	Atomic Layer Deposition of LaF ₃ Thin Films using La(thd) ₃ and TiF ₄ as Precursors. <i>Chemical Vapor Deposition</i> , 2008 , 14, 85-91		28
238	Coating of Highly Porous Fiber Matrices by Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 2008 , 14, 347-352		32
237	The Atomic Layer Deposition of HfO ₂ and ZrO ₂ using Advanced Metallocene Precursors and H ₂ O as the Oxygen Source. <i>Chemical Vapor Deposition</i> , 2008 , 14, 358-365		44
236	Selective surface patterning with an electric discharge in the fabrication of microfluidic structures. <i>Angewandte Chemie - International Edition</i> , 2008 , 47, 7442-5	16.4	8
235	Surface modification of thermoplastics by atomic layer deposition of Al ₂ O ₃ and TiO ₂ thin films. <i>European Polymer Journal</i> , 2008 , 44, 3564-3570	5.2	81
234	Selective-area atomic layer deposition with microcontact printed self-assembled octadecyltrichlorosilane monolayers as mask layers. <i>Thin Solid Films</i> , 2008 , 517, 972-975	2.2	56
233	Novel ALD Process for Depositing CaF ₂ Thin Films. <i>Chemistry of Materials</i> , 2007 , 19, 3387-3392	9.6	74
232	Radical Enhanced Atomic Layer Deposition of Tantalum Oxide. <i>Chemistry of Materials</i> , 2007 , 19, 2316-2326		19
231	A pyrazolate-based metalorganic tantalum precursor that exhibits high thermal stability and its use in the atomic layer deposition of Ta ₂ O ₅ . <i>Journal of the American Chemical Society</i> , 2007 , 129, 12370-1	16.4	36
230	Study of a novel ALD process for depositing MgF ₂ thin films. <i>Journal of Materials Chemistry</i> , 2007 , 17, 5077		59
229	H ₂ S modified atomic layer deposition process for photocatalytic TiO ₂ thin films. <i>Journal of Materials Chemistry</i> , 2007 , 17, 1361-1371		57
228	Hollow Inorganic Nanospheres and Nanotubes with Tunable Wall Thicknesses by Atomic Layer Deposition on Self-Assembled Polymeric Templates. <i>Advanced Materials</i> , 2007 , 19, 102-106	24	118
227	Radical-Enhanced Atomic Layer Deposition of Silver Thin Films Using Phosphine-Adducted Silver Carboxylates. <i>Chemical Vapor Deposition</i> , 2007 , 13, 408-413		60
226	Atomic Layer Deposition of Titanium Disulfide Thin Films. <i>Chemical Vapor Deposition</i> , 2007 , 13, 163-168		31
225	Atomic Layer Deposition of BaTiO ₃ Thin Films Effect of Barium Hydroxide Formation. <i>Chemical Vapor Deposition</i> , 2007 , 13, 239-246		49
224	Radical Enhanced Atomic Layer Deposition of Titanium Dioxide. <i>Chemical Vapor Deposition</i> , 2007 , 13, 152-157		41
223	Atomic Layer Deposition of Gadolinium Oxide Films. <i>Chemical Vapor Deposition</i> , 2007 , 13, 546-552		16
222	Influence of TiO ₂ incorporation in HfO ₂ and Al ₂ O ₃ based capacitor dielectrics. <i>Thin Solid Films</i> , 2007 , 515, 6447-6451	2.2	30

221	Exploitation of atomic layer deposition for nanostructured materials. <i>Materials Science and Engineering C</i> , 2007 , 27, 1504-1508	8.3	62
220	Atomic layer deposition of ZrO ₂ and HfO ₂ on deep trenched and planar silicon. <i>Microelectronic Engineering</i> , 2007 , 84, 2010-2013	2.5	31
219	Experimental observations of temperature-dependent flat band voltage transients on high-k dielectrics. <i>Microelectronics Reliability</i> , 2007 , 47, 653-656	1.2	12
218	Si/Al ₂ O ₃ /ZnO:Al capacitor arrays formed in electrochemically etched porous Si by atomic layer deposition. <i>Microelectronic Engineering</i> , 2007 , 84, 313-318	2.5	36
217	Crystal structures and thermal properties of Ba(1,2,4-t-Bu ₃ C ₅ H ₂) ₂ and Sr(1,2,4-t-Bu ₃ C ₅ H ₂) ₂ : Precursors for atomic layer deposition. <i>Journal of Organometallic Chemistry</i> , 2007 , 692, 5256-5262	2.3	25
216	Zone-doubling technique to produce ultrahigh-resolution x-ray optics. <i>Physical Review Letters</i> , 2007 , 99, 264801	7.4	140
215	Electrical characterization of Al _x Ti _y O _z mixtures and Al ₂ O ₃ /TiO ₂ /Al ₂ O ₃ nanolaminates. <i>Journal of Applied Physics</i> , 2007 , 102, 114114	2.5	34
214	Electrical Characterization of High-k Dielectrics by Means of Flat-Band Voltage Transient Recording. <i>Materials Research Society Symposia Proceedings</i> , 2007 , 996, 1		
213	Electrical Properties of Atomic-Layer-Deposited Thin Gadolinium Oxide High-k Gate Dielectrics. <i>Journal of the Electrochemical Society</i> , 2007 , 154, G207	3.9	34
212	Ruthenium/aerogel nanocomposites via atomic layer deposition. <i>Nanotechnology</i> , 2007 , 18, 055303	3.4	68
211	Atomic Layer Deposition of Nanostructured TiO ₂ Photocatalysts via Template Approach. <i>Chemistry of Materials</i> , 2007 , 19, 1816-1820	9.6	108
210	A Novel Atomic Layer Deposition Process for Depositing Metal Fluoride Thin Films 2007 ,		3
209	Free-standing inductive grid filter for infrared radiation rejection. <i>Microelectronic Engineering</i> , 2006 , 83, 1339-1342	2.5	9
208	Atomic Layer Deposition and Properties of Lanthanum Oxide and Lanthanum-Aluminum Oxide Films. <i>Chemical Vapor Deposition</i> , 2006 , 12, 158-164		51
207	Self-Assembled Octadecyltrimethoxysilane Monolayers Enabling Selective-Area Atomic Layer Deposition of Iridium. <i>Chemical Vapor Deposition</i> , 2006 , 12, 415-417		54
206	Ir/Oxide/Cellulose Composites for Catalytic Purposes Prepared by Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 2006 , 12, 419-422		40
205	Rapid Coating of Through-Porous Substrates by Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 2006 , 12, 655-658		28
204	Iridium Barriers for Direct Copper Electrodeposition in Damascene Processing. <i>Electrochemical and Solid-State Letters</i> , 2006 , 9, C48-C50		41

203	Quantum dot manipulation in a single-walled carbon nanotube using a carbon nanotube gate. <i>Applied Physics Letters</i> , 2006 , 89, 233107	3.4	5
202	Electrodeposition of Cu on Ru Barrier Layers for Damascene Processing. <i>Journal of the Electrochemical Society</i> , 2006 , 153, C37	3.9	98
201	Iridium Barriers for Direct Copper Electrodeposition in Damascene Processing. <i>ECS Transactions</i> , 2006 , 1, 57-61	1	2
200	Diffusion Barrier Properties of Atomic Layer Deposited Ultrathin Ta[sub 2]O[sub 5] and TiO[sub 2] Films. <i>Journal of the Electrochemical Society</i> , 2006 , 153, G304	3.9	30
199	HfO[sub 2] Films Grown by ALD Using Cyclopentadienyl-Type Precursors and H[sub 2]O or O[sub 3] as Oxygen Source. <i>Journal of the Electrochemical Society</i> , 2006 , 153, F39	3.9	33
198	Atomic Layer Deposition of Ferroelectric Bismuth Titanate Bi ₄ Ti ₃ O ₁₂ Thin Films. <i>Chemistry of Materials</i> , 2006 , 18, 3883-3888	9.6	43
197	Scale-up of the BaTiO ₃ ALD Process onto 200 mm Wafer. <i>ECS Transactions</i> , 2006 , 1, 137-141	1	8
196	Rare-earth oxide thin films for gate dielectrics in microelectronics. <i>Journal of Alloys and Compounds</i> , 2006 , 418, 27-34	5.7	118
195	Experimental investigation of the electrical properties of atomic layer deposited hafnium-rich silicate films on n-type silicon. <i>Journal of Applied Physics</i> , 2006 , 100, 094107	2.5	9
194	Transparent superhydrophobic surfaces by self-assembly of hydrophobic monolayers on nanostructured surfaces. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2006 , 203, 1453-1458 ^{1.6}		21
193	Antifouling properties of TiO ₂ : Photocatalytic decomposition and adhesion of fatty and rosin acids, sterols and lipophilic wood extractives. <i>Colloids and Surfaces A: Physicochemical and Engineering Aspects</i> , 2006 , 291, 162-176	5.1	31
192	Atomic layer deposition of TiO ₂ /N _x thin films for photocatalytic applications. <i>Journal of Photochemistry and Photobiology A: Chemistry</i> , 2006 , 177, 68-75	4.7	105
191	Characterisation of the Al ₂ O ₃ films deposited by ultrasonic spray pyrolysis and atomic layer deposition methods for passivation of 4HSiC devices. <i>Microelectronics Reliability</i> , 2006 , 46, 743-755	1.2	21
190	Atomic layer deposition of calcium oxide and calcium hafnium oxide films using calcium cyclopentadienyl precursor. <i>Thin Solid Films</i> , 2006 , 500, 322-329	2.2	29
189	Titania and titania-silver nanoparticle deposits made by Liquid Flame Spray and their functionality as photocatalyst for organic- and biofilm removal. <i>Catalysis Letters</i> , 2006 , 111, 127-132	2.8	43
188	Destruction of <i>Deinococcus geothermalis</i> biofilm by photocatalytic ALD and sol-gel TiO ₂ surfaces. <i>Journal of Industrial Microbiology and Biotechnology</i> , 2006 , 33, 261-8	4.2	37
187	DISORDERED STRUCTURE AND DENSITY OF GAP STATES IN HIGH-PERMITTIVITY THIN SOLID FILMS 2006 , 123-134		
186	ELECTRICAL DEFECTS IN ATOMIC LAYER DEPOSITED HfO ₂ FILMS ON SILICON: INFLUENCE OF PRECURSOR CHEMISTRIES AND SUBSTRATE TREATMENT 2006 , 287-298		

185	Aging of electroluminescent ZnS:Mn thin films deposited by atomic layer deposition processes. <i>Journal of Applied Physics</i> , 2005 , 98, 113526	2.5	12
184	Radical-Enhanced Atomic Layer Deposition of Metallic Copper Thin Films. <i>Journal of the Electrochemical Society</i> , 2005 , 152, G25	3.9	54
183	Low-Temperature Deposition of Aluminum Oxide by Radical Enhanced Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2005 , 152, F90	3.9	63
182	Controlled growth of HfO ₂ thin films by atomic layer deposition from cyclopentadienyl-type precursor and water. <i>Journal of Materials Chemistry</i> , 2005 , 15, 2271		55
181	In situ quadrupole mass spectrometry study of atomic-layer deposition of ZrO ₂ using Cp ₂ Zr(CH ₃) ₂ and water. <i>Langmuir</i> , 2005 , 21, 7321-5	4	38
180	Atomic layer deposition in nanometer-level replication of cellulosic substances and preparation of photocatalytic TiO ₂ /cellulose composites. <i>Journal of the American Chemical Society</i> , 2005 , 127, 14178-9	16.4	175
179	In situ reaction mechanism studies on the atomic layer deposition of Al ₂ O ₃ from (CH ₃) ₂ AlCl and water. <i>Langmuir</i> , 2005 , 21, 3498-502	4	21
178	Thin Film Deposition Methods for CuInSe ₂ Solar Cells. <i>Critical Reviews in Solid State and Materials Sciences</i> , 2005 , 30, 1-31	10.1	235
177	Electrical characterization of hafnium oxide and hafnium-rich silicate films grown by atomic layer deposition. <i>Microelectronics Reliability</i> , 2005 , 45, 949-952	1.2	6
176	Atomic layer deposition rate, phase composition and performance of HfO ₂ films on noble metal and alkoxyated silicon substrates. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2005 , 118, 112-116	3.1	18
175	Recent developments in the MOCVD and ALD of rare earth oxides and silicates. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2005 , 118, 97-104	3.1	46
174	Comparative study on electrical properties of atomic layer deposited high-permittivity materials on silicon substrates. <i>Thin Solid Films</i> , 2005 , 474, 222-229	2.2	12
173	Engineering structure and properties of hafnium oxide films by atomic layer deposition temperature. <i>Thin Solid Films</i> , 2005 , 479, 1-11	2.2	34
172	Atomic layer deposition of hafnium dioxide thin films from hafnium tetrakis(dimethylamide) and water. <i>Thin Solid Films</i> , 2005 , 491, 328-338	2.2	66
171	The growth and diffusion barrier properties of atomic layer deposited NbN _x thin films. <i>Thin Solid Films</i> , 2005 , 491, 235-241	2.2	40
170	New Approach to the ALD of Bismuth Silicates; Bi(CH ₂ SiMe ₃) ₃ Acting as a Precursor for both Bismuth and Silicon. <i>Chemical Vapor Deposition</i> , 2005 , 11, 362-367		16
169	Atomic Layer Deposition of Molybdenum Nitride Thin Films for Cu Metallizations. <i>Journal of the Electrochemical Society</i> , 2005 , 152, G361	3.9	47
168	Atomic Layer Deposition and Characterization of HfO ₂ Films on Noble Metal Film Substrates. <i>Journal of the Electrochemical Society</i> , 2005 , 152, F75	3.9	19

167	Diffractive optics in industry and research: novel components for optical security systems 2005 ,		1
166	ALD of Rhodium Thin Films from Rh(acac)[sub 3] and Oxygen. <i>Electrochemical and Solid-State Letters</i> , 2005 , 8, C99		49
165	Characterization of Aluminium and Titanium Oxides Deposited on 4H-SiC by Atomic Layer Deposition Technique. <i>Materials Science Forum</i> , 2005 , 483-485, 701-704	0.4	12
164	Structural and dielectric properties of thin ZrO ₂ films on silicon grown by atomic layer deposition from cyclopentadienyl precursor. <i>Journal of Applied Physics</i> , 2004 , 95, 84-91	2.5	66
163	Effect of selected atomic layer deposition parameters on the structure and dielectric properties of hafnium oxide films. <i>Journal of Applied Physics</i> , 2004 , 96, 5298-5307	2.5	58
162	Dielectric Permittivity and Intercalation Parameters of Li Ion Intercalated Atomic Layer Deposited ZrO[sub 2]. <i>Journal of the Electrochemical Society</i> , 2004 , 151, F54	3.9	2
161	Atomic layer deposition of noble metals: Exploration of the low limit of the deposition temperature. <i>Journal of Materials Research</i> , 2004 , 19, 3353-3358	2.5	140
160	ALD of Ta(Si)N Thin Films Using TDMAS as a Reducing Agent and as a Si Precursor. <i>Journal of the Electrochemical Society</i> , 2004 , 151, G523	3.9	11
159	Atomic Layer Deposition of Strontium Tantalate Thin Films from Bimetallic Precursors and Water. <i>Journal of the Electrochemical Society</i> , 2004 , 151, F69	3.9	26
158	Properties of HfO[sub 2] Thin Films Grown by ALD from Hafnium tetrakis(ethylmethanamide) and Water. <i>Journal of the Electrochemical Society</i> , 2004 , 151, F189	3.9	56
157	Synthesis and characterisation of cyclopentadienyl complexes of barium: precursors for atomic layer deposition of BaTiO ₃ . <i>Dalton Transactions</i> , 2004 , 1181-8	4.3	47
156	Crystallization in hafnia- and zirconia-based systems. <i>Physica Status Solidi (B): Basic Research</i> , 2004 , 241, 2268-2278	1.3	134
155	Atomic Layer Deposition of Hafnium Dioxide Films from Hafnium Hydroxylamide and Water. <i>Chemical Vapor Deposition</i> , 2004 , 10, 91-96		25
154	Atomic Layer Deposition of Ruthenium Thin Films from Ru(thd) ₃ and Oxygen. <i>Chemical Vapor Deposition</i> , 2004 , 10, 215-219		127
153	Atomic Layer Deposition of Photocatalytic TiO ₂ Thin Films from Titanium Tetramethoxide and Water. <i>Chemical Vapor Deposition</i> , 2004 , 10, 143-148		190
152	Hafnium silicon oxide films prepared by atomic layer deposition. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2004 , 109, 2-5	3.1	14
151	Growth of Cu thin films by the successive ionic layer adsorption and reaction (SILAR) method. <i>Thin Solid Films</i> , 2004 , 460, 36-40	2.2	8
150	XPS and electroluminescence studies on SrS _{1-x} Sex and ZnS _{1-x} Sex thin films deposited by atomic layer deposition technique. <i>Journal of Crystal Growth</i> , 2004 , 260, 440-446	1.6	15

149	Evaluation of New Aminoalkoxide Precursors for Atomic Layer Deposition. Growth of Zirconium Dioxide Thin Films and Reaction Mechanism Studies. <i>Chemistry of Materials</i> , 2004 , 16, 5630-5636	9.6	27
148	Evaluation of a Praseodymium Precursor for Atomic Layer Deposition of Oxide Dielectric Films. <i>Chemistry of Materials</i> , 2004 , 16, 5162-5168	9.6	50
147	Bismuth precursors for atomic layer deposition of bismuth-containing oxide films. <i>Journal of Materials Chemistry</i> , 2004 , 14, 3191-3197		71
146	Atomic Layer Deposition of Iridium Thin Films. <i>Journal of the Electrochemical Society</i> , 2004 , 151, G489	3.9	123
145	Some recent developments in the MOCVD and ALD of high- ϵ dielectric oxides. <i>Journal of Materials Chemistry</i> , 2004 , 14, 3101-3112		77
144	Properties of Oxide Film Atomic Layer Deposited from Tetraethoxy Silane, Hafnium Halides, and Water. <i>Journal of the Electrochemical Society</i> , 2004 , 151, F98	3.9	23
143	Electroluminescent SrS and BaS Thin Films Deposited by ALD Using Cyclopentadienyl Precursors. <i>Journal of the Electrochemical Society</i> , 2004 , 151, H221	3.9	11
142	Atomic layer deposition of HfO ₂ thin films and nanolayered HfO ₂ /Al ₂ O ₃ /Nb ₂ O ₅ dielectrics. <i>Journal of Materials Science: Materials in Electronics</i> , 2003 , 14, 361-367	2.1	29
141	Ruthenium Thin Films Grown by Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 2003 , 9, 45-49		219
140	Atomic Layer Deposition of Hafnium Dioxide Films Using Hafnium Bis(2-butanolate)bis(1-methoxy-2-methyl-2-propanolate) and Water. <i>Chemical Vapor Deposition</i> , 2003 , 9, 315-320		43
139	Chemie der Atomlagenabscheidung (Atomic Layer Deposition): jüngste Entwicklungen. <i>Angewandte Chemie</i> , 2003 , 115, 5706-5713	3.6	30
138	Atomic layer deposition chemistry: recent developments and future challenges. <i>Angewandte Chemie - International Edition</i> , 2003 , 42, 5548-54	16.4	843
137	Rare-earth oxide thin films as gate oxides in MOSFET transistors. <i>Journal of Solid State Chemistry</i> , 2003 , 171, 170-174	3.3	98
136	Conductance transient, capacitance-voltage and deep-level transient spectroscopy characterization of atomic layer deposited hafnium and zirconium oxide thin films. <i>Solid-State Electronics</i> , 2003 , 47, 1623-1629	1.7	18
135	Electrochemical preparation of In and Al doped ZnO thin films for CuInSe ₂ solar cells. <i>Thin Solid Films</i> , 2003 , 434, 20-23	2.2	55
134	Atomic layer deposition growth of zirconium doped In ₂ O ₃ films. <i>Thin Solid Films</i> , 2003 , 440, 152-154	2.2	25
133	Reaction Mechanism Studies on Atomic Layer Deposition of Ruthenium and Platinum. <i>Electrochemical and Solid-State Letters</i> , 2003 , 6, C130		186
132	Atomic Layer Deposition of Hafnium Dioxide Films from 1-Methoxy-2-methyl-2-propanolate Complex of Hafnium. <i>Chemistry of Materials</i> , 2003 , 15, 1722-1727	9.6	46

131	Atomic Layer Deposition of Platinum Thin Films. <i>Chemistry of Materials</i> , 2003 , 15, 1924-1928	9.6	329
130	On the interface quality of MIS structures fabricated from Atomic Layer Deposition of HfO ₂ , Ta ₂ O ₅ and Nb ₂ O ₅ /Ta ₂ O ₅ /Nb ₂ O ₅ dielectric thin films. <i>Materials Research Society Symposia Proceedings</i> , 2003 , 786, 3181		
129	Liquid injection MOCVD and ALD studies of single source Sr-Nb and Sr-Ta precursors. <i>Materials Research Society Symposia Proceedings</i> , 2003 , 784, 411		
128	Blue- and green-emitting SrS:Cu electroluminescent devices deposited by the atomic layer deposition technique. <i>Journal of Applied Physics</i> , 2003 , 94, 3862-3868	2.5	9
127	Atomic layer deposition. <i>Series in Materials Science and Engineering</i> , 2003 ,		1
126	Reaction Mechanism Studies on Titanium Isopropoxide/Water Atomic Layer Deposition Process. <i>Chemical Vapor Deposition</i> , 2002 , 8, 21		115
125	Atomic Layer Deposition of Hafnium Dioxide Films from Hafnium Tetrakis(ethylmethanamide) and Water. <i>Chemical Vapor Deposition</i> , 2002 , 8, 199-204		174
124	Atomic layer deposition of TiO ₂ thin films from TiI ₄ and H ₂ O. <i>Applied Surface Science</i> , 2002 , 193, 277-286.	6.7	69
123	Atomic layer deposition (ALD): from precursors to thin film structures. <i>Thin Solid Films</i> , 2002 , 409, 138-146.	4.2	958
122	Influence of thickness and growth temperature on the properties of zirconium oxide films grown by atomic layer deposition on silicon. <i>Thin Solid Films</i> , 2002 , 410, 53-60	2.2	31
121	Comparison of hafnium oxide films grown by atomic layer deposition from iodide and chloride precursors. <i>Thin Solid Films</i> , 2002 , 416, 72-79	2.2	114
120	Properties of hafnium oxide films grown by atomic layer deposition from hafnium tetraiodide and oxygen. <i>Journal of Applied Physics</i> , 2002 , 92, 5698-5703	2.5	54
119	Tert-butylamine and Allylamine as Reductive Nitrogen Sources in Atomic Layer Deposition of TaN Thin Films. <i>Journal of Materials Research</i> , 2002 , 17, 107-114	2.5	34
118	Atomic-Layer Deposition of ZrO ₂ Thin Films Using New Alkoxide Precursors. <i>Materials Research Society Symposia Proceedings</i> , 2002 , 716, 351		6
117	Atomic Layer Deposition of SrS and BaS Thin Films Using Cyclopentadienyl Precursors. <i>Chemistry of Materials</i> , 2002 , 14, 1937-1944	9.6	31
116	In Situ Mass Spectrometry Study on Surface Reactions in Atomic Layer Deposition of TiN and Ti(Al)N Thin Films. <i>Chemistry of Materials</i> , 2002 , 14, 281-287	9.6	26
115	Reaction Mechanism Studies on the Atomic Layer Deposition of Zr _x Ti _y O _z Using the Novel Metal Halide/Metal Alkoxide Approach. <i>Langmuir</i> , 2002 , 18, 10046-10048	4	14
114	Compensation of temperature effects in quartz crystal microbalance measurements. <i>Applied Physics Letters</i> , 2002 , 80, 521-523	3.4	44

113	Atomic layer deposition 2002 , 103-159		232
112	Atomic Layer Deposition of Titanium Nitride Thin Films Using tert-Butylamine and Allylamine as Reductive Nitrogen Sources. <i>Electrochemical and Solid-State Letters</i> , 2002 , 5, C4		24
111	Atomic layer deposition of Al ₂ O ₃ films using AlCl ₃ and Al(OiPr) ₃ as precursors. <i>Journal of Materials Chemistry</i> , 2002 , 12, 1415-1418		30
110	Reaction mechanism studies on the zirconium chloride/water atomic layer deposition process. <i>Journal of Materials Chemistry</i> , 2002 , 12, 1484-1489		50
109	Influence of growth temperature on properties of zirconium dioxide films grown by atomic layer deposition. <i>Journal of Applied Physics</i> , 2002 , 92, 1833-1840	2.5	89
108	Atomic layer deposition of ZrO ₂ thin films using a new alkoxide precursor. <i>Journal of Non-Crystalline Solids</i> , 2002 , 303, 24-28	3.9	37
107	Atomic layer deposition of Al ₂ O ₃ , ZrO ₂ , Ta ₂ O ₅ , and Nb ₂ O ₅ based nanolayered dielectrics. <i>Journal of Non-Crystalline Solids</i> , 2002 , 303, 35-39	3.9	38
106	Electrochemical quartz crystal microbalance study on cyclic electrodeposition of PbS thin-films. <i>Thin Solid Films</i> , 2001 , 386, 32-40	2.2	15
105	Atomic Layer Deposition of SrTiO ₃ Thin Films from a Novel Strontium Precursor Strontium-bis(tri-isopropyl cyclopentadienyl). <i>Chemical Vapor Deposition</i> , 2001 , 7, 75-80		96
104	Trimethylaluminum as a Reducing Agent in the Atomic Layer Deposition of Ti(Al)N Thin Films. <i>Chemical Vapor Deposition</i> , 2001 , 7, 211		45
103	Atomic layer deposition of zirconium oxide from zirconium tetraiodide, water and hydrogen peroxide. <i>Journal of Crystal Growth</i> , 2001 , 231, 262-272	1.6	73
102	Thermogravimetric Study of Volatile Precursors For Chemical Thin Film Deposition. Estimation of vapor pressures and source temperatures. <i>Magyar Áprilad Kémiayek</i> , 2001 , 64, 955-964	0	13
101	Electrochemical Quartz Crystal Microbalance Study of the Electrodeposition Mechanisms of CuInSe ₂ Thin Films. <i>Journal of the Electrochemical Society</i> , 2001 , 148, C110	3.9	21
100	Atomic Layer Deposition of Ta(Al)N(C) Thin Films Using Trimethylaluminum as a Reducing Agent. <i>Journal of the Electrochemical Society</i> , 2001 , 148, G566	3.9	48
99	(Ta _{1-x} Nb _x) ₂ O ₅ films produced by atomic layer deposition: Temperature dependent dielectric spectroscopy and room-temperature IV characteristics. <i>Journal of Applied Physics</i> , 2001 , 90, 4532-4542	2.5	22
98	In Situ Mass Spectrometry Study on Atomic Layer Deposition from Metal (Ti, Ta, and Nb) Ethoxides and Water. <i>Chemistry of Materials</i> , 2001 , 13, 817-823	9.6	52
97	In Situ Quartz Crystal Microbalance and Quadrupole Mass Spectrometry Studies of Atomic Layer Deposition of Aluminum Oxide from Trimethylaluminum and Water. <i>Langmuir</i> , 2001 , 17, 6506-6509	4	137
96	Dielectric Properties of Zirconium Oxide Grown by Atomic Layer Deposition from Iodide Precursor. <i>Journal of the Electrochemical Society</i> , 2001 , 148, F227	3.9	43

95	Effects of post-deposition treatments on the photoactivity of CuInSe ₂ thin films deposited by the induced co-deposition mechanism. <i>Journal of Materials Chemistry</i> , 2001 , 11, 668-672		33
94	In Situ Quadrupole Mass Spectrometry and Quartz Crystal Microbalance Studies on the Atomic Layer Deposition of Titanium Dioxide from Titanium Tetrachloride and Water. <i>Chemistry of Materials</i> , 2001 , 13, 4506-4511	9.6	90
93	Atomic Layer Deposition of Zirconium Titanium Oxide from Titanium Isopropoxide and Zirconium Chloride. <i>Chemistry of Materials</i> , 2001 , 13, 1528-1532	9.6	33
92	Development of Dielectric Properties of Niobium Oxide, Tantalum Oxide, and Aluminum Oxide Based Nanolayered Materials. <i>Journal of the Electrochemical Society</i> , 2001 , 148, F35	3.9	90
91	In situ characterization of atomic layer deposition of SrTiO ₃ . <i>European Physical Journal Special Topics</i> , 2001 , 11, Pr3-923-Pr3-930		16
90	Electroluminescent Phosphors 2001 , 2541-2548		
89	Atomic Layer CVD in the BiTiO ₃ System. <i>Chemical Vapor Deposition</i> , 2000 , 6, 139-145		48
88	Low-Temperature Deposition of Zirconium Oxide Based Nanocrystalline Films by Alternate Supply of Zr[OC(CH ₃) ₃] ₄ and H ₂ O. <i>Chemical Vapor Deposition</i> , 2000 , 6, 297-302		83
87	Atomic Layer Deposition of Titanium Oxide from TiI ₄ and H ₂ O ₂ . <i>Chemical Vapor Deposition</i> , 2000 , 6, 303-310		50
86	Electrochemical quartz crystal microbalance study of the electrodeposition mechanisms of Cu ₂ Se thin films. <i>Electrochimica Acta</i> , 2000 , 45, 3737-3748	6.7	46
85	Influence of atomic layer deposition parameters on the phase content of Ta ₂ O ₅ films. <i>Journal of Crystal Growth</i> , 2000 , 212, 459-468	1.6	48
84	PbTe electrodeposition studied by combined electrochemical quartz crystal microbalance and cyclic voltammetry. <i>Journal of Electroanalytical Chemistry</i> , 2000 , 482, 139-148	4.1	38
83	Effect of water dose on the atomic layer deposition rate of oxide thin films. <i>Thin Solid Films</i> , 2000 , 368, 1-7	2.2	227
82	Characterization of titanium dioxide atomic layer growth from titanium ethoxide and water. <i>Thin Solid Films</i> , 2000 , 370, 163-172	2.2	69
81	Titanium isopropoxide as a precursor for atomic layer deposition: characterization of titanium dioxide growth process. <i>Applied Surface Science</i> , 2000 , 161, 385-395	6.7	182
80	Atomic layer deposition of oxide thin films with metal alkoxides as oxygen sources. <i>Science</i> , 2000 , 288, 319-21	33.3	415
79	One-Step Electrodeposition of Cu ₂ Se and CuInSe ₂ Thin Films by the Induced Co-deposition Mechanism. <i>Journal of the Electrochemical Society</i> , 2000 , 147, 1080	3.9	52
78	Use of 1,1-Dimethylhydrazine in the Atomic Layer Deposition of Transition Metal Nitride Thin Films. <i>Journal of the Electrochemical Society</i> , 2000 , 147, 3377	3.9	93

77	In Situ Mass Spectrometry Study on Surface Reactions in Atomic Layer Deposition of Al ₂ O ₃ Thin Films from Trimethylaluminum and Water. <i>Langmuir</i> , 2000 , 16, 4034-4039	4	99
76	Atomic Layer Deposition and Chemical Vapor Deposition of Tantalum Oxide by Successive and Simultaneous Pulsing of Tantalum Ethoxide and Tantalum Chloride. <i>Chemistry of Materials</i> , 2000 , 12, 1914-1920	9.6	49
75	Electrochemical quartz crystal microbalance and cyclic voltammetry studies on PbSe electrodeposition mechanisms. <i>Journal of Materials Chemistry</i> , 2000 , 10, 519-525		23
74	Real-Time Monitoring in Atomic Layer Deposition of TiO ₂ from TiI ₄ and H ₂ O. <i>Langmuir</i> , 2000 , 16, 8122-8128	4	40
73	Atomic Layer Deposition of Titanium Oxide from TiI ₄ and H ₂ O ₂ 2000 , 6, 303		6
72	In situ characterization of atomic layer deposition processes by a mass spectrometer. <i>European Physical Journal Special Topics</i> , 1999 , 09, Pr8-1021-Pr8-1028		21
71	Photo- and electroluminescence of SrS:Cu and SrS:Ag,Cu,Ga thin films. <i>Journal of Applied Physics</i> , 1999 , 86, 5017-5025	2.5	20
70	Use of atomic layer epitaxy for fabrication of Si/TiN/Cu structures. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 1999 , 17, 2122		21
69	Improved blue luminescence in Ag-codoped SrS:Ce thin films made by atomic layer epitaxy and ion implantation. <i>Applied Physics Letters</i> , 1999 , 74, 2298-2300	3.4	8
68	Chapter 3 Materials in Thin Film Electroluminescent Devices. <i>Semiconductors and Semimetals</i> , 1999 , 107-1082		10
67	Enhanced Growth Rate in Atomic Layer Epitaxy of Indium Oxide and Indium-Tin Oxide Thin Films. <i>Electrochemical and Solid-State Letters</i> , 1999 , 1, 156		36
66	Modification of ALE-grown SrS thin films by ion implantation of Cu and codopants. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1999 , 148, 715-719	1.2	2
65	Perfectly Conformal TiN and Al ₂ O ₃ Films Deposited by Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 1999 , 5, 7-9		254
64	Properties of atomic layer deposited (Ta _{1-x} Nb _x) ₂ O ₅ solid solution films and Ta ₂ O ₅ /Nb ₂ O ₅ nanolaminates. <i>Journal of Applied Physics</i> , 1999 , 86, 5656-5662	2.5	50
63	Growth of SrTiO ₃ and BaTiO ₃ Thin Films by Atomic Layer Deposition. <i>Electrochemical and Solid-State Letters</i> , 1999 , 2, 504		133
62	ALD precursor chemistry : Evolution and future challenges. <i>European Physical Journal Special Topics</i> , 1999 , 09, Pr8-837-Pr8-852		24
61	Atomic layer epitaxy - a valuable tool for nanotechnology?. <i>Nanotechnology</i> , 1999 , 10, 19-24	3.4	249
60	Atomic layer deposited thin films for corrosion protection. <i>European Physical Journal Special Topics</i> , 1999 , 09, Pr8-493-Pr8-499		63

59	Properties of [Mg ₂ (thd) ₄] as a Precursor for Atomic Layer Deposition of MgO Thin Films and Crystal Structures of [Mg ₂ (thd) ₄] and [Mg(thd) ₂ (EtOH) ₂]. <i>Chemistry of Materials</i> , 1999 , 11, 1846-1852	9.6	44
58	Cyclic Electrodeposition of PbS Thin Films. <i>Journal of the Electrochemical Society</i> , 1999 , 146, 2522-2525	3.9	20
57	Controlled Growth of TaN, Ta ₃ N ₅ , and TaOxNy Thin Films by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 1999 , 11, 1712-1718	9.6	150
56	Niobium Oxide Thin Films Grown by Atomic Layer Epitaxy. <i>Chemical Vapor Deposition</i> , 1998 , 4, 29-34		26
55	Atomic Layer Epitaxy Growth of BaS and BaS:Ce Thin Films from In Situ Synthesized Ba(thd) ₂ . <i>Chemical Vapor Deposition</i> , 1998 , 4, 227-233		7
54	Influence of sol and surface properties on in vitro bioactivity of sol-gel-derived TiO ₂ and TiO ₂ -SiO ₂ films deposited by dip-coating method. <i>Journal of Biomedical Materials Research Part B</i> , 1998 , 42, 295-302		112
53	Electrodeposition of PbTe thin films. <i>Thin Solid Films</i> , 1998 , 326, 78-82	2.2	58
52	Electrodeposition of lead selenide thin films. <i>Journal of Materials Chemistry</i> , 1998 , 8, 651-654		59
51	Elemental characterization of electroluminescent SrS:Ce thin films. <i>Journal of Applied Physics</i> , 1998 , 84, 1029-1035	2.5	14
50	Deposition of molybdenum thin films by an alternate supply of MoCl ₅ and Zn. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1998 , 16, 2845-2850	2.9	32
49	Solid Solution CdxZn _{1-x} S Thin Films Grown by Atomic Layer Epitaxy and Successive Ionic Layer Adsorption and Reaction Techniques. <i>Materials Science Forum</i> , 1998 , 287-288, 367-372	0.4	2
48	Atomic Layer Epitaxy Growth of TiN Thin Films from TiI ₄ and NH ₃ . <i>Journal of the Electrochemical Society</i> , 1998 , 145, 2914-2920	3.9	64
47	Niobium Oxide Thin Films Grown by Atomic Layer Epitaxy. <i>Chemical Vapor Deposition</i> , 1998 , 04, 29-34		53
46	Atomic Layer Epitaxy Growth of BaS and BaS:Ce Thin Films from In Situ Synthesized Ba(thd) ₂ . <i>Chemical Vapor Deposition</i> , 1998 , 04, 227-233		18
45	Deposition of copper films by an alternate supply of CuCl and Zn. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1997 , 15, 2330-2333	2.9	59
44	Fluorine Implantation of Atomic Layer Epitaxy Grown In ₂ O ₃ Films. <i>Journal of the Electrochemical Society</i> , 1997 , 144, L140-L141	3.9	2
43	Properties of Ta ₂ O ₅ -Based Dielectric Nanolaminates Deposited by Atomic Layer Epitaxy. <i>Journal of the Electrochemical Society</i> , 1997 , 144, 300-306	3.9	107
42	[Ca(Thd) ₂ (Tetraen)]: A Monomeric Precursor for Deposition of CaS Thin Films. <i>Chemistry of Materials</i> , 1997 , 9, 1234-1240	9.6	27

41	Atomic layer epitaxy growth of aluminum oxide thin films from a novel Al(CH ₃) ₂ Cl precursor and H ₂ O. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1997 , 15, 2214-2218	2.9	85
40	Properties of (Nb _{1-x} Tax) ₂ O ₅ solid solutions and (Nb _{1-x} Tax) ₂ O ₅ -ZrO ₂ nanolaminates grown by Atomic Layer Epitaxy. <i>Scripta Materialia</i> , 1997 , 8, 785-793		37
39	In situ study of atomic layer epitaxy growth of tantalum oxide thin films from Ta(OC ₂ H ₅) ₅ and H ₂ O. <i>Applied Surface Science</i> , 1997 , 112, 236-242	6.7	66
38	Effects of intermediate zinc pulses on properties of TiN and NbN films deposited by atomic layer epitaxy. <i>Applied Surface Science</i> , 1997 , 120, 199-212	6.7	40
37	Complementary analysis of ALE-grown SrS based thin film electroluminescent structures with ion beam methods. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 132, 685-696	1.2	9
36	ALE growth of ZnS _{1-x} Sex thin films by substituting surface sulfur with elemental selenium. <i>Applied Surface Science</i> , 1997 , 112, 154-158	6.7	19
35	Modifying ALE grown In ₂ O ₃ films by benzoyl fluoride pulses. <i>Applied Surface Science</i> , 1997 , 112, 231-235	6.7	22
34	Advanced ALE processes of amorphous and polycrystalline films. <i>Applied Surface Science</i> , 1997 , 112, 223-230	6.7	77
33	AFM studies on ZnS thin films grown by atomic layer epitaxy. <i>Applied Surface Science</i> , 1997 , 120, 43-50	6.7	82
32	ALE Growth of Transparent Conductors. <i>Materials Research Society Symposia Proceedings</i> , 1996 , 426, 513		31
31	Characterization of etching procedure in preparation of CdTe solar cells. <i>Solar Energy Materials and Solar Cells</i> , 1996 , 44, 177-190	6.4	38
30	Low temperature deposition of AlN films by an alternate supply of trimethyl aluminum and ammonia. <i>Chemical Vapor Deposition</i> , 1996 , 2, 277-283		54
29	AFM and STM studies on In ₂ O ₃ and ITO thin films deposited by atomic layer epitaxy. <i>Applied Surface Science</i> , 1996 , 99, 91-98	6.7	33
28	Synthesis of oxide thin films and overlayers by atomic layer epitaxy for advanced applications. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 1996 , 41, 23-29	3.1	117
27	Introducing atomic layer epitaxy for the deposition of optical thin films. <i>Thin Solid Films</i> , 1996 , 289, 250-255		69
26	Studies on the morphology of Al ₂ O ₃ thin films grown by atomic layer epitaxy. <i>Thin Solid Films</i> , 1996 , 286, 54-58	2.2	49
25	Analysis of AlN thin films by combining TOF-ERDA and NRB techniques. <i>Thin Solid Films</i> , 1996 , 289, 159-165		55
24	Tailoring the dielectric properties of HfO ₂ /Ta ₂ O ₅ nanolaminates. <i>Applied Physics Letters</i> , 1996 , 68, 3737-3739	3.7	194

23	ALE deposition of indium tin oxide thin films. <i>Vacuum</i> , 1995 , 46, 887	3.7	4
22	Atomic Layer Epitaxy Growth of AlN Thin Films. <i>European Physical Journal Special Topics</i> , 1995 , 05, C5-1021-C5-1027		
21	Atomic Layer Epitaxy in Deposition of Various Oxide and Nitride Thin Films. <i>European Physical Journal Special Topics</i> , 1995 , 05, C5-937-C5-951		13
20	Atomic Layer Epitaxy Growth of TiN Thin Films. <i>Journal of the Electrochemical Society</i> , 1995 , 142, 2731-2737	3.7	125
19	Growth of Indium-Tin-Oxide Thin Films by Atomic Layer Epitaxy. <i>Journal of the Electrochemical Society</i> , 1995 , 142, 3538-3541	3.9	38
18	Atomic Layer Epitaxy Growth of Tantalum Oxide Thin Films from Ta (OC ₂ H ₅) ₅ and H ₂ O. <i>Journal of the Electrochemical Society</i> , 1995 , 142, 1670-1675	3.9	112
17	Comparison Between CVD and ALE Produced TiO ₂ Cathodes in Zn/(PEO) ₄ ZnCl ₂ /TiO ₂ ,SnO ₂ or ITO Galvanic Cells. <i>European Physical Journal Special Topics</i> , 1995 , 05, C5-1133-C5-1139		2
16	Growth of In ₂ O ₃ Thin Films by Atomic Layer Epitaxy. <i>Journal of the Electrochemical Society</i> , 1994 , 141, 3210-3213	3.9	59
15	Development of crystallinity and morphology in hafnium dioxide thin films grown by atomic layer epitaxy. <i>Thin Solid Films</i> , 1994 , 250, 72-80	2.2	175
14	Surface roughness reduction in atomic layer epitaxy growth of titanium dioxide thin films. <i>Thin Solid Films</i> , 1994 , 249, 155-162	2.2	44
13	Zirconium dioxide thin films deposited by ALE using zirconium tetrachloride as precursor. <i>Applied Surface Science</i> , 1994 , 75, 333-340	6.7	137
12	Growth of In ₂ S ₃ thin films by atomic layer epitaxy. <i>Applied Surface Science</i> , 1994 , 82-83, 122-125	6.7	115
11	NbCl ₅ as a precursor in atomic layer epitaxy. <i>Applied Surface Science</i> , 1994 , 82-83, 468-474	6.7	45
10	Atomic layer epitaxy growth of titanium dioxide thin films from titanium ethoxide. <i>Chemistry of Materials</i> , 1994 , 6, 556-561	9.6	95
9	Titanium isopropoxide as a precursor in atomic layer epitaxy of titanium dioxide thin films. <i>Chemistry of Materials</i> , 1993 , 5, 1174-1181	9.6	259
8	The Effect of Calcination on the Surface Composition and Structure of Titanium Dioxide Coated Mica Particles. <i>Journal of Solid State Chemistry</i> , 1993 , 103, 160-169	3.3	10
7	Atomic force microscopy study of titanium dioxide thin films grown by atomic layer epitaxy. <i>Thin Solid Films</i> , 1993 , 228, 32-35	2.2	76
6	Thermoanalytical studies on TiO ₂ -mica pigments. <i>Thermochimica Acta</i> , 1993 , 214, 19-26	2.9	3

- 5 Growth of titanium dioxide thin films by atomic layer epitaxy. *Thin Solid Films*, **1993**, 225, 288-295 2.2 276
- 4 Electrical characterization of atomic-layer-deposited hafnium silicate for alternative gate dielectric application 1
- 3 Chapter 4: Atomic Layer Deposition 158-206 5
- 2 Poster: Advances in Technology and Characterization 665-692
- 1 Molecular Layer Deposition of Thermally Stable Polybenzimidazole-Like Thin Films and Nanostructures. *Advanced Materials Interfaces*, 2200370 4.6